

[See all 2 Products in Family](#)

13.5nm, 25.4mm Dia, 5° AOI, EUV Flat Mirror



Extreme Ultraviolet (EUV) Flat Mirrors

Stock #38-759 10 In Stock

-

1

+

£2,200⁰⁰

ADD TO CART

Volume Pricing	
Qty 1+	£2,200.00 each
Need More?	Request Quote

! Prices shown are exclusive of VAT/local taxes

Product Downloads

General	
Flat Mirror	Type:
Physical & Mechanical Properties	
25.40 ±0.25	Diameter (mm):
Commercial Polish	Back Surface:
Clear Aperture (%):	

90	
Fine Ground	Edges:
3	Parallelism (arcmin):
<5 RMS	Surface Roughness (□):
6.35 ±0.508	Thickness (mm):
Optical Properties	
λ/10 @ 632.8nm	Surface Flatness (P-V):
Single Crystal Silicon	Substrate: □
10-5	Surface Quality:
R _{abs} >60% @ 13.5nm, 5° (s-pol)	Coating Specification:
Mb/Si Multilayer Top Layer: Silicon	Coating:
Metal/Semiconductor	Coating Type:
5	Angle of Incidence (°):
13.5	Design Wavelength DWL (nm):
13.18 - 13.68	Wavelength Range (nm):
0.50	Full Width-Half Max FWHM (nm):
>60	Reflection at DWL (%):
Electrical	
92	Center Energy (eV):
Regulatory Compliance	
View	Certificate of Conformance:

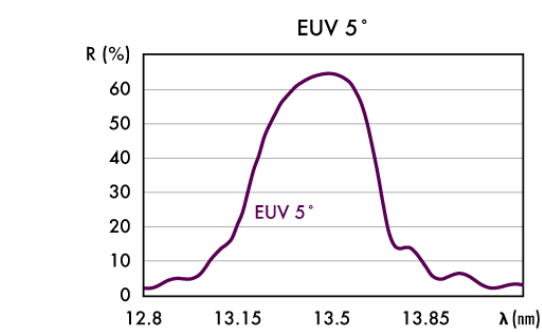
Product Details

- Maximum Achievable Reflection at 13.5nm
- Designed for EUV Beam Steering and Harmonic Separation
- 5° and 45° AOI Versions Available

Extreme Ultraviolet (EUV) Flat Mirrors are multilayer mirrors designed for maximum achievable reflectance at the design wavelength and angle of incidence. These mirrors feature a coating deposited on a super-polished single crystal silicon substrate and surface roughness less than 3□ RMS. The 45° AOI mirrors are useful for steering s-polarized beams, while the 5° AOI mirrors may be used with unpolarized beams. Applications for EUV mirrors include Coherent Diffractive Imaging (CDI) and materials science research. Extreme Ultraviolet (EUV) Flat Mirrors can also serve as harmonic selectors for High Harmonic Generation (HHG) beams.

Note: Test data from each mirror's production run sample included.

Technical Information



Compatible Mounts

